



3D ASIC development

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on behalf of the AGIPD collaboration

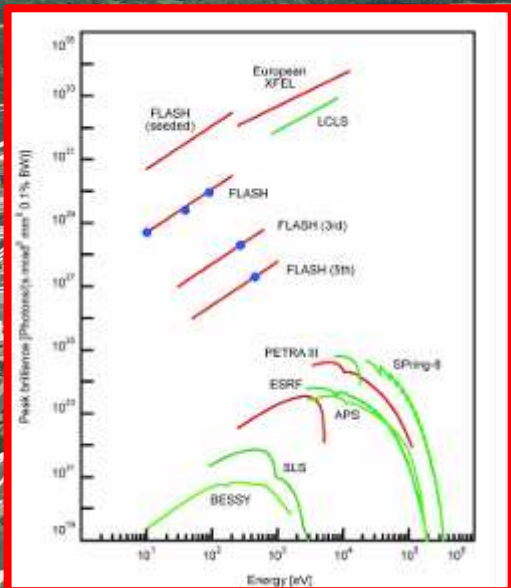
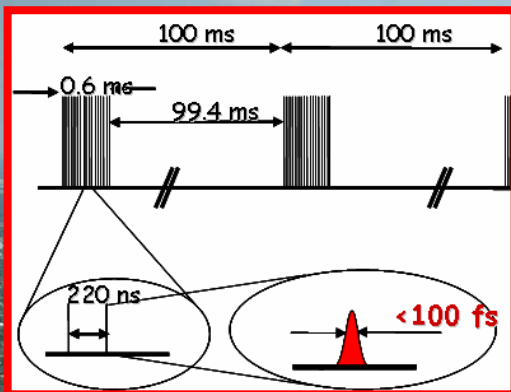


Outline



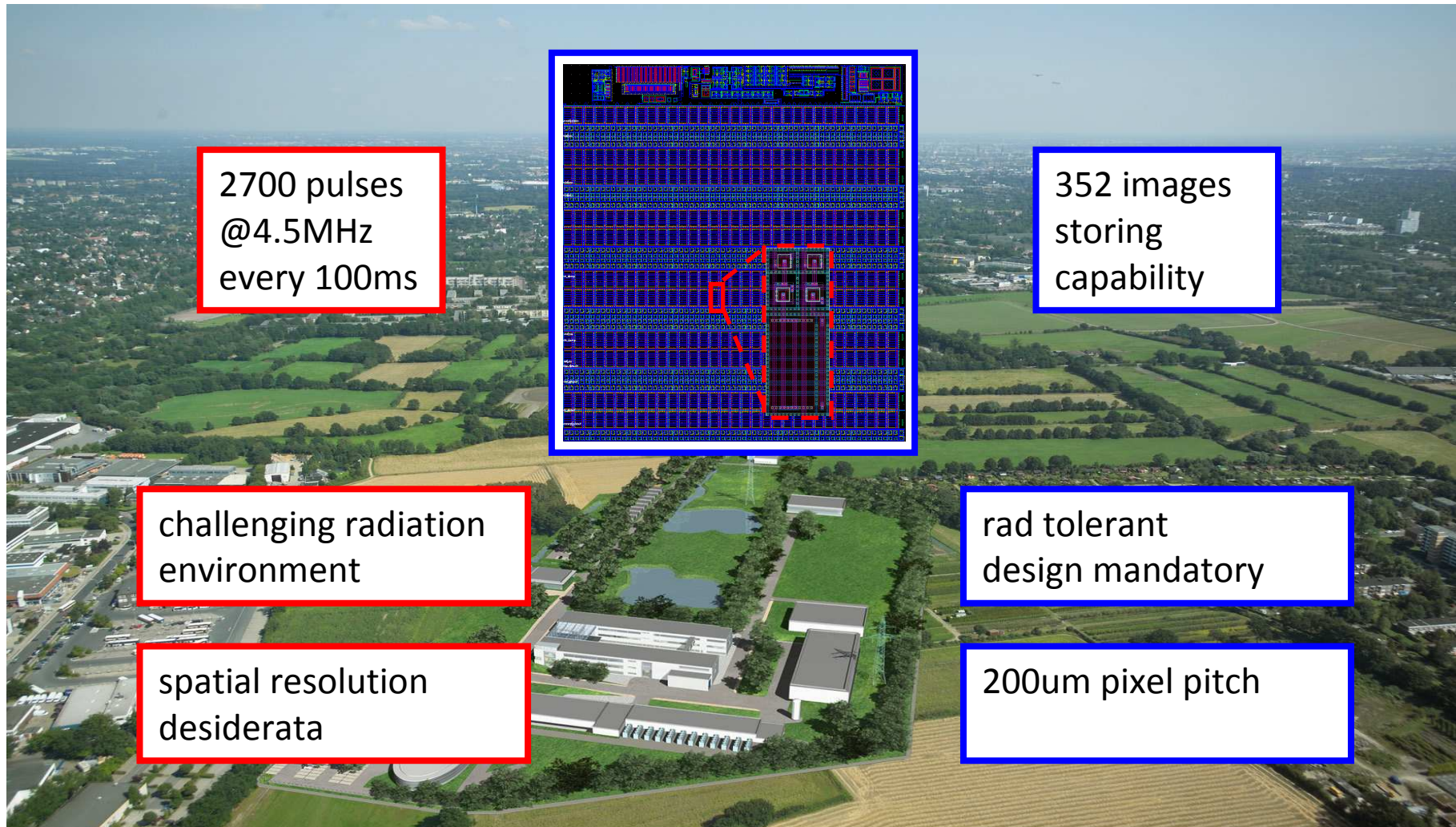
- The goal and the obstacles to overcome
 - X-ray sensors for advanced FEL
 - Adaptive Gain Integrating Pixel Detector (AGIPD)
 - 3DIC: a possible path to the solution
- Design and test of 2-tier detector prototype
 - TSVs & tier-to-tier contacts
 - vertically integrated test circuits, matrix prototype
- Conclusion

The Motivation



1Mpixel, 200 μm pitch
Adaptable Gain $\times(100)$
single-photon resolution
 10^4 ph dyn rng
Rad tol 100MGy~1GGy
Burst imaging 4.5Mfps
(tested upto 6.5Mfps)
In-pixel Memory (352 img)

The Motivation



2700 pulses
@4.5MHz
every 100ms

352 images
storing
capability

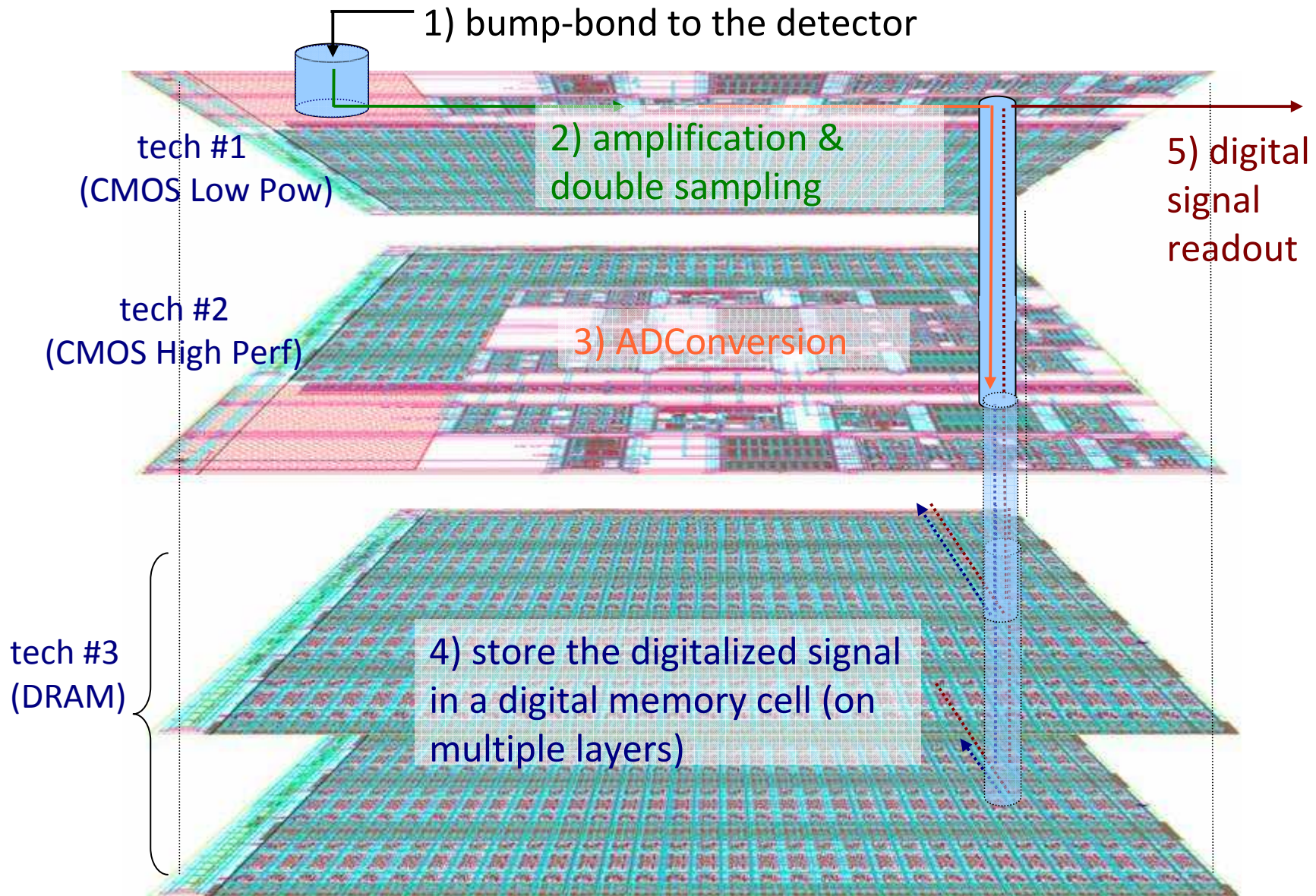
challenging radiation
environment

rad tolerant
design mandatory

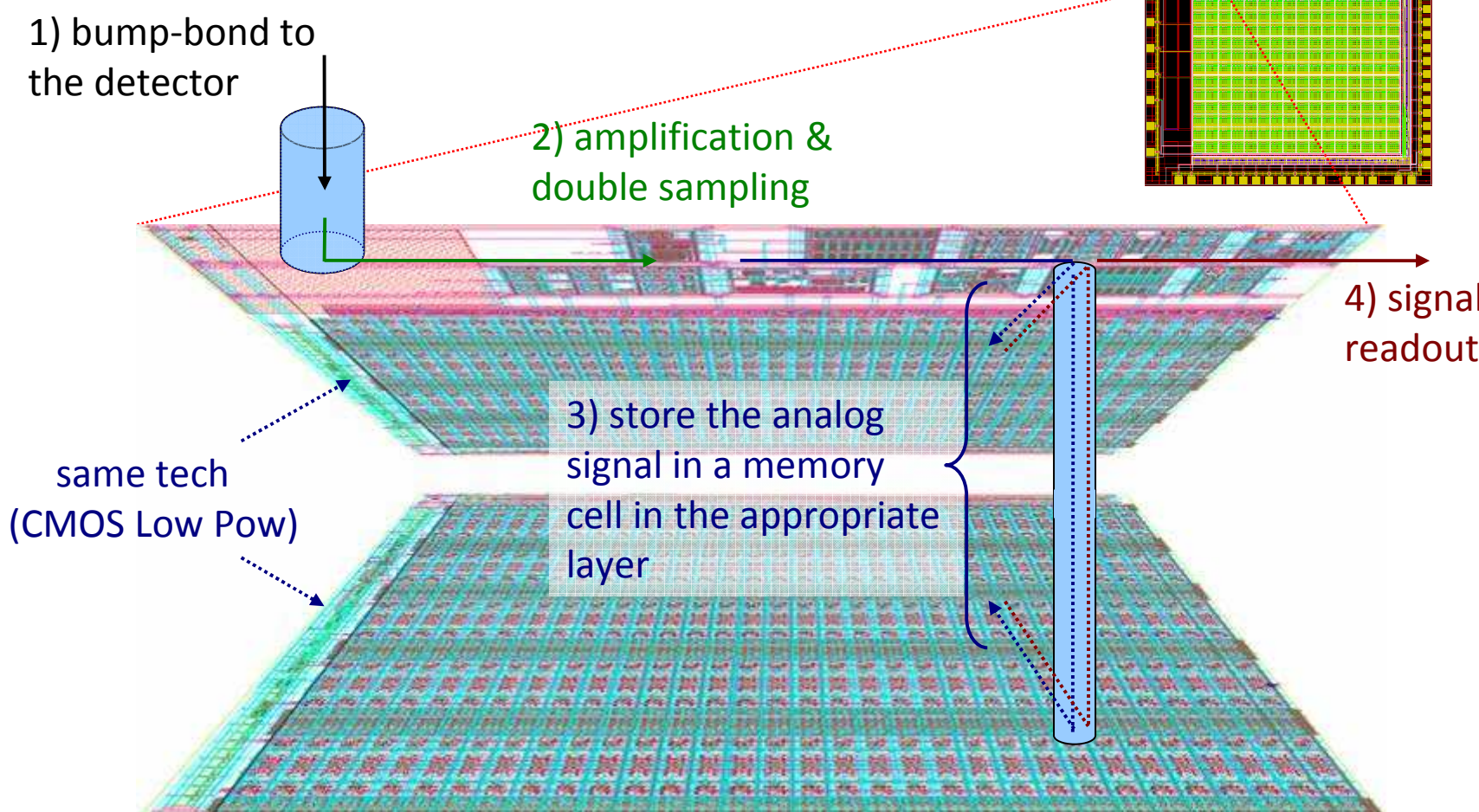
spatial resolution
desiderata

200um pixel pitch

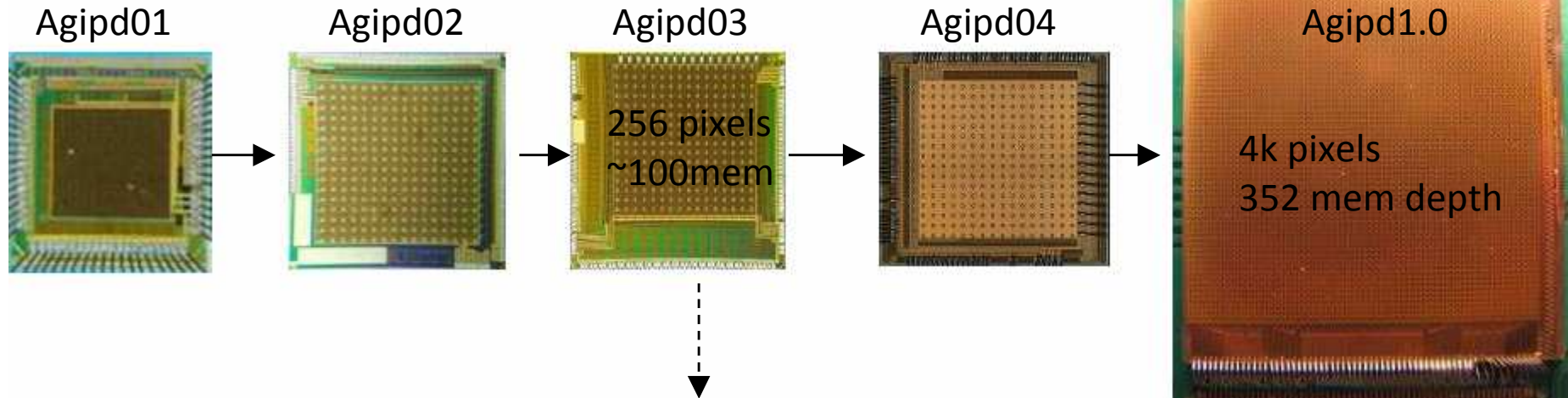
A possible solution (long term goal)



The first step

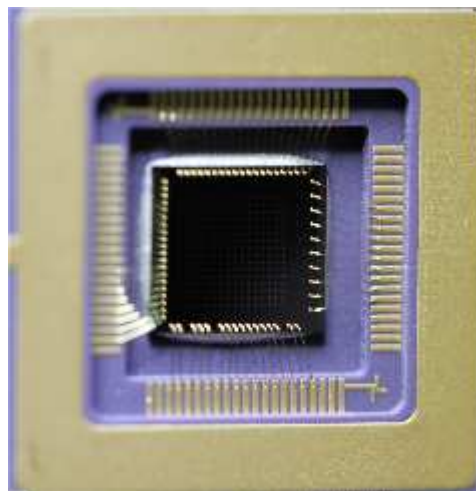


A path toward the solution



GF 130nm CMOS Low Power
ARM SC library
Tezzaron FaStack
double-tier

T13C11 MPWrun, via CMP
submitted 2011
delivered Jan 2014



3D-AGIPD0

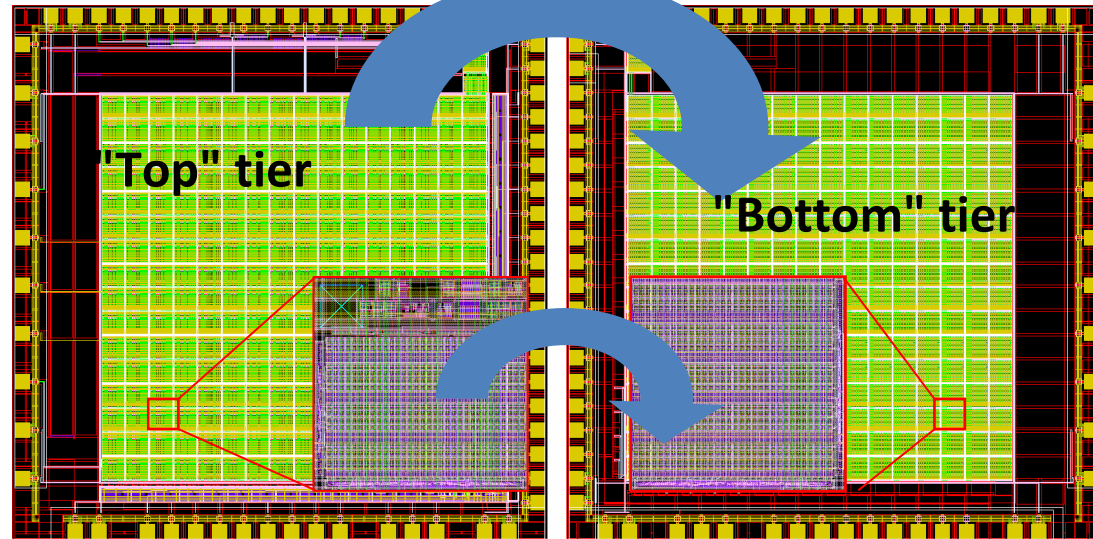
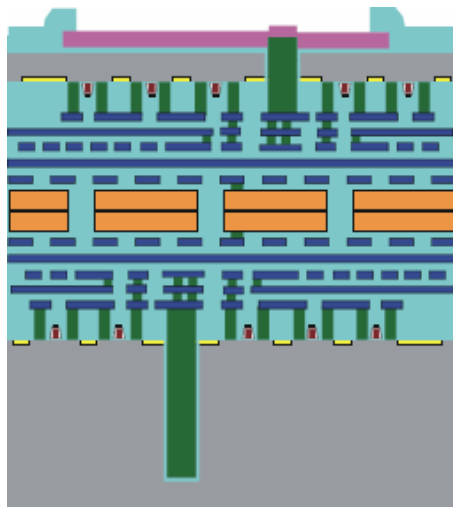
test structures +
256 pixels matrix
200um pitch
544 um depth

simplified architecture: fixed
gain (but reserving the space
for multiple-gain circuits;
equivalent memcell area)

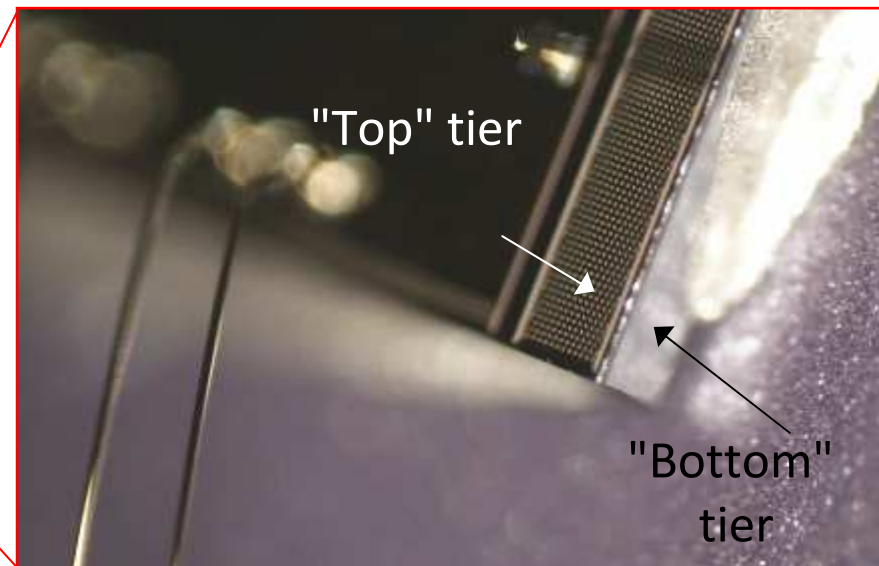
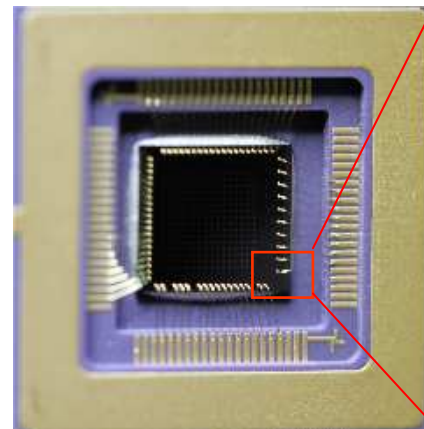
The process at a glance



Tezzaron process used



- 2x planar chip manufacture
 - via-middle TSVs
- stacking and face-to-face coupling
- back-grinding of the top tier and exposition of the TSVs
- Pad definition



The process at a glance

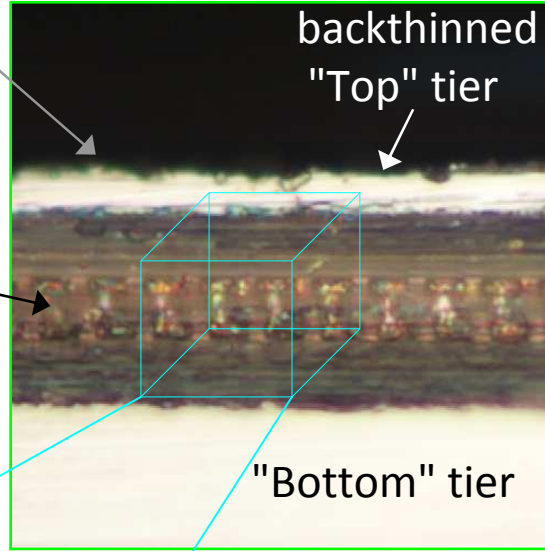


Al wire/bump bonding pads

tier-to-tier contacts

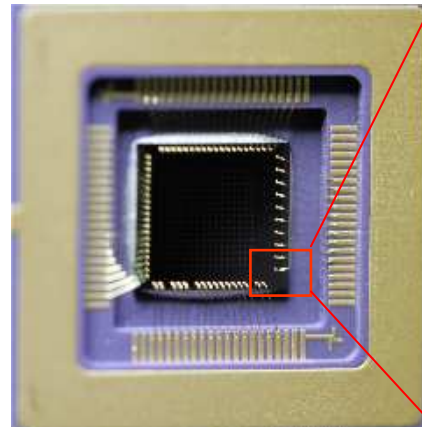
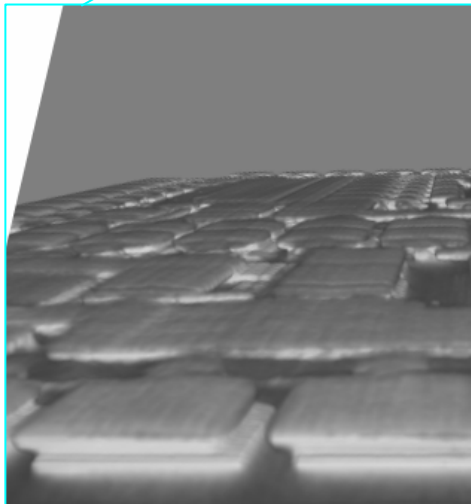
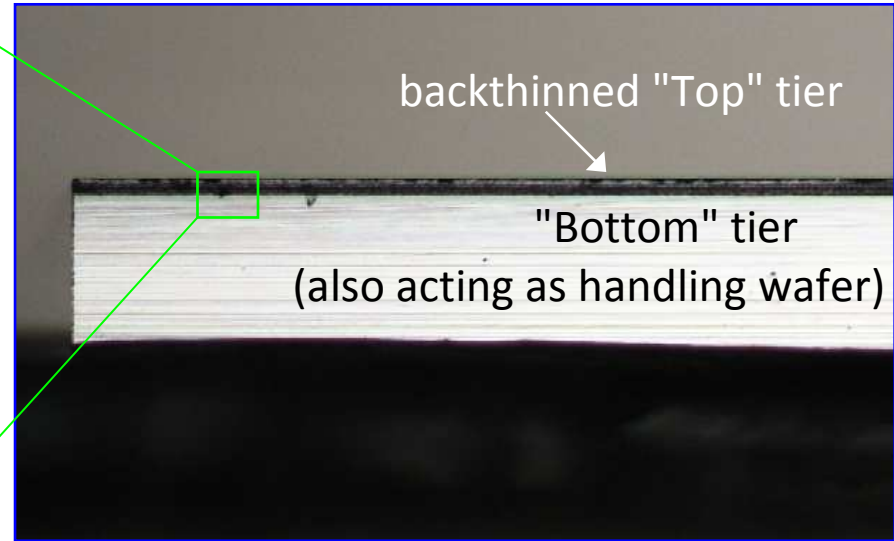
backthinned "Top" tier

"Bottom" tier



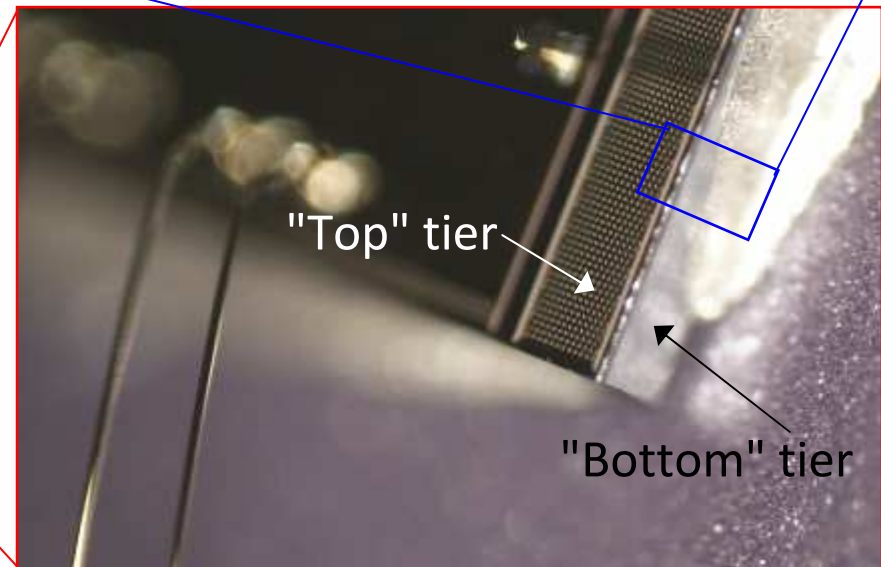
backthinned "Top" tier

"Bottom" tier
(also acting as handling wafer)

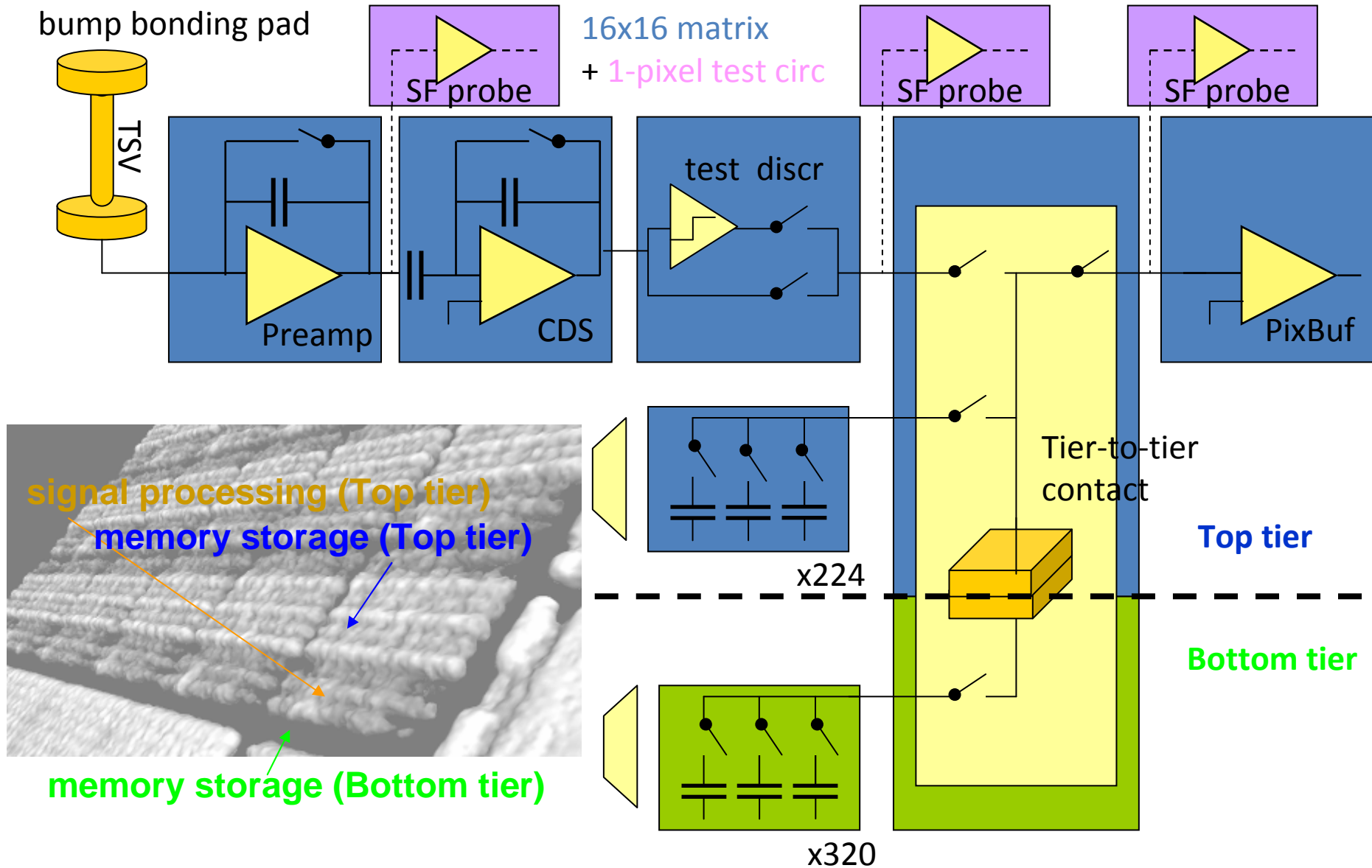


"Top" tier

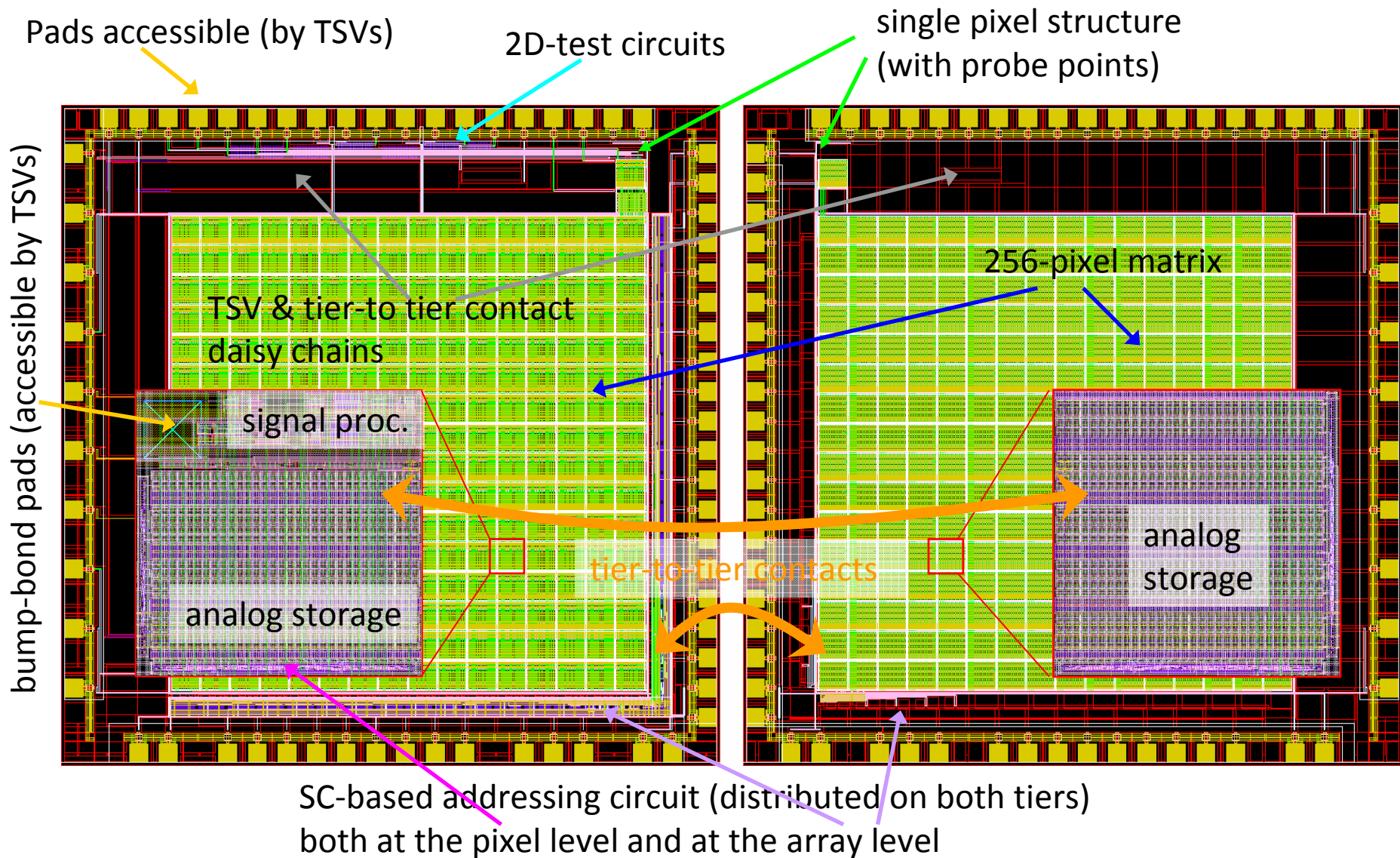
"Bottom" tier



pixel architecture



chip architecture



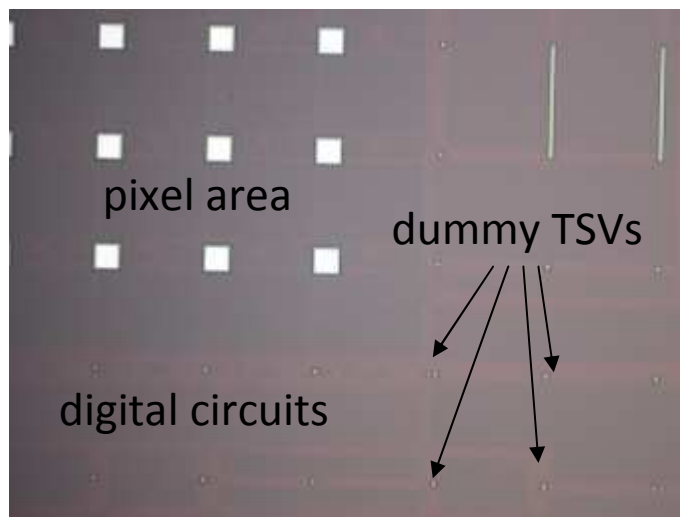
TSV contacts evaluation



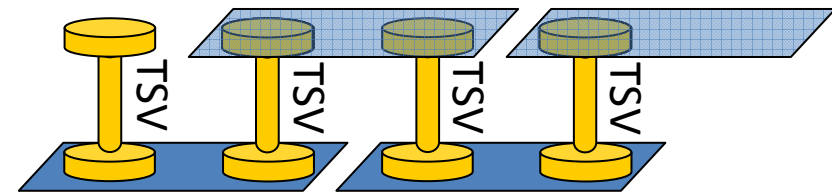
"via middle" TSVs \varnothing 1.2 μm , landing on M1

locally: TSV-to-TSV distance down to $\sim 4\mu\text{m}$
however, globally: "uniform" density of TSVs recommended (\rightarrow uniform resistance to grinding)

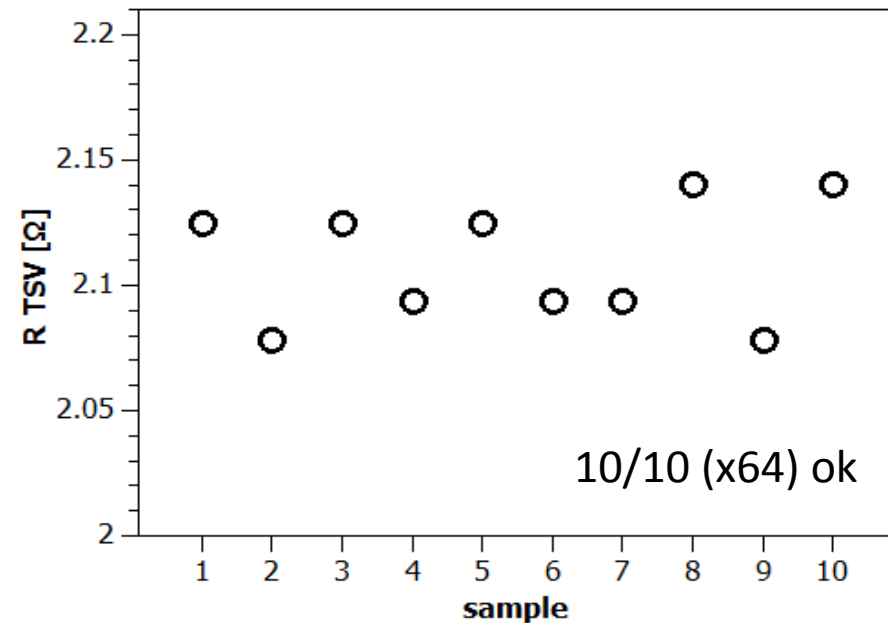
\rightarrow designer constraint: dummy TSVs



10x test structure for TSV evaluation: daisy chain of 64 TSVs, by connected M1/backM.



TSV average resistance



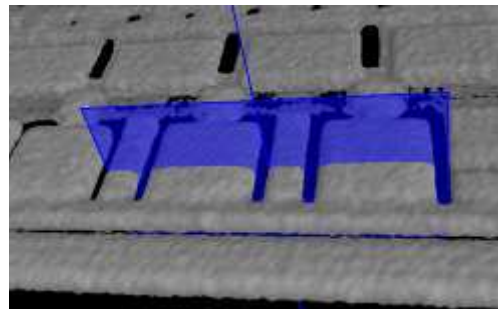
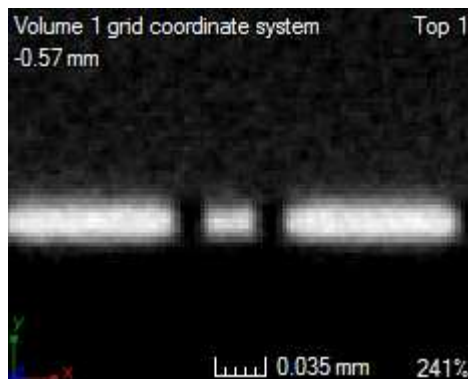
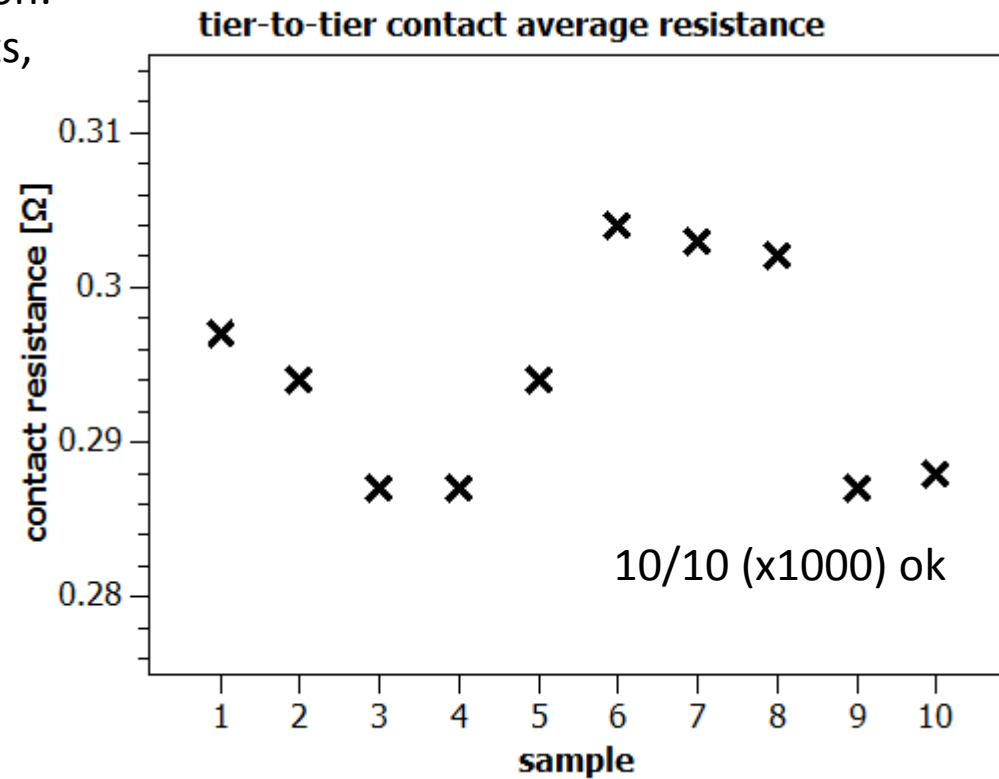
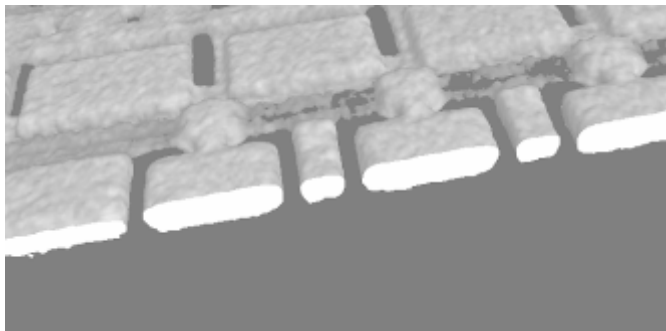
measured on 10 packaged samples
no broken chain, avg R 2.1 Ω /TSV

Tier-to-tier contact evaluation



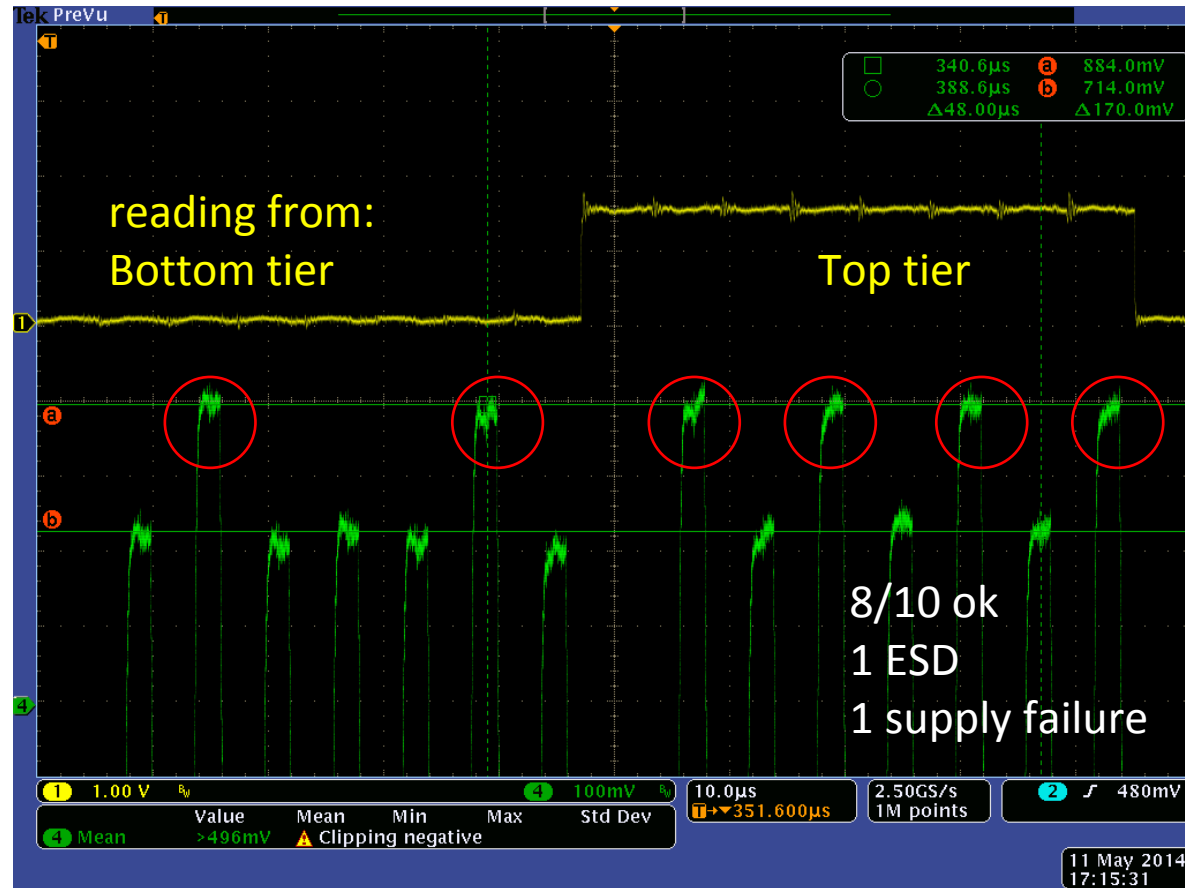
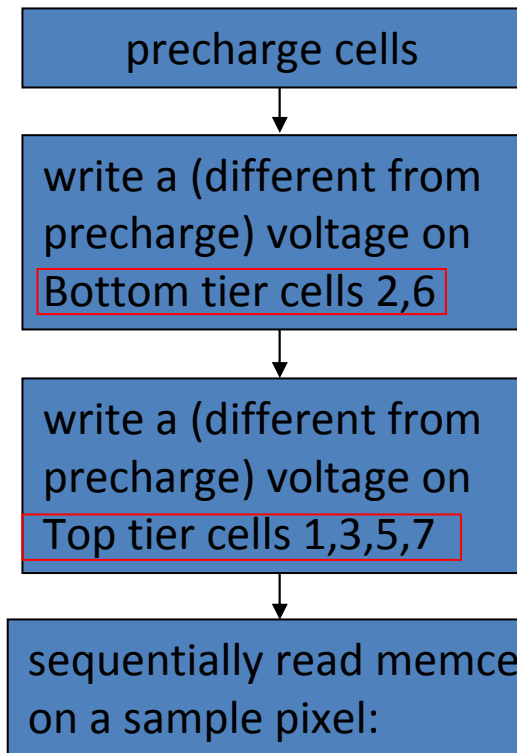
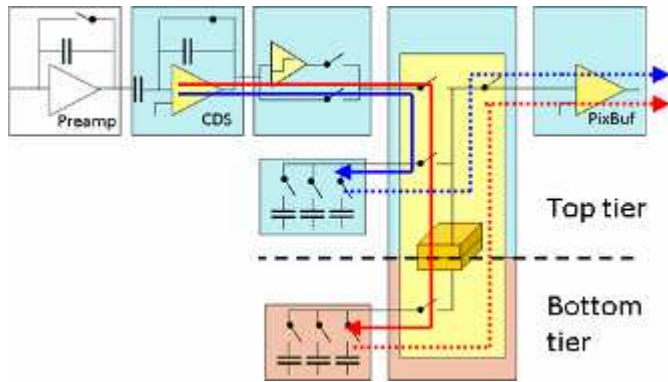
10x test structure for contact evaluation:
daisy chain of 1000 tier-to-tier contacts,
connected in series using M5.

measured independently
on 10 packaged samples
no broken chain



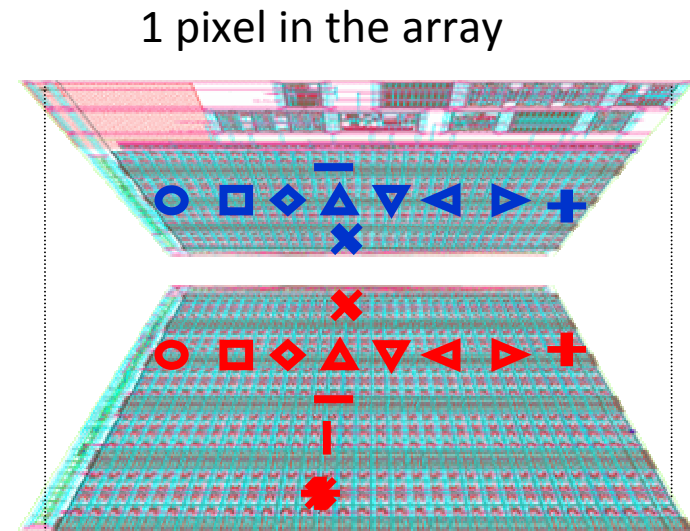
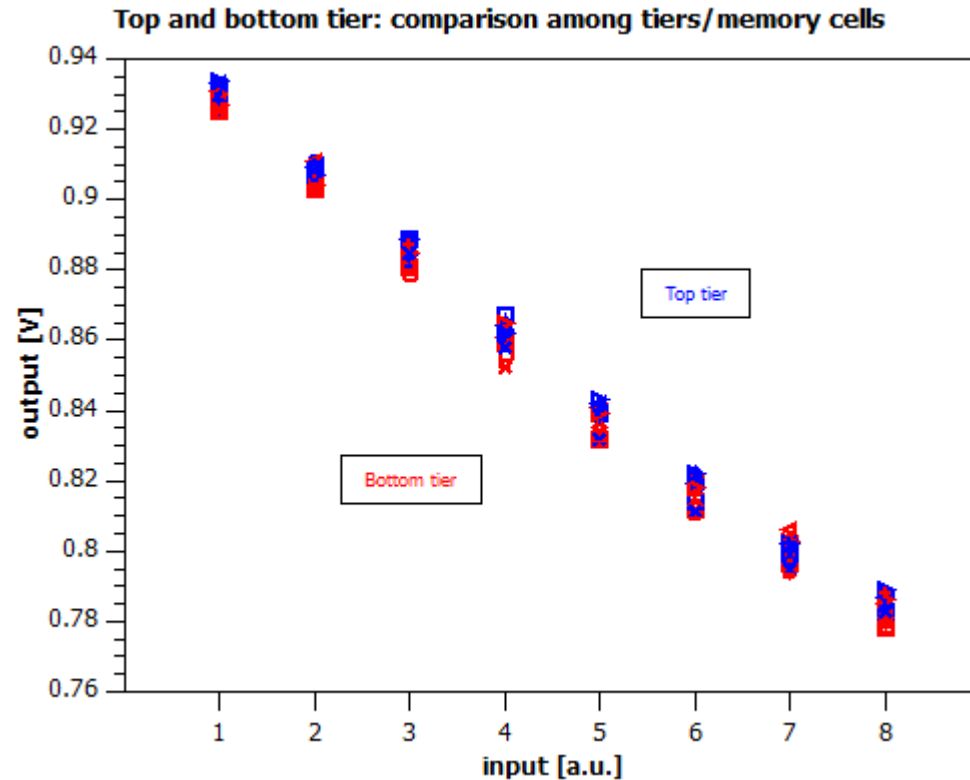
x-ray tomography (F. Beckmann,
DESY) also suggest better alignment

Pixel matrix write-read example



- Bottom,1
- Bottom,2
- Bottom,3
- Bottom,4
- Bottom,5
- Bottom,6
- Bottom,7
- Top,1
- Top,2
- Top,3
- Top,4
- Top,5
- Top,6
- Top,7

Top/Bottom tier: memory cell-to-memory cell variations

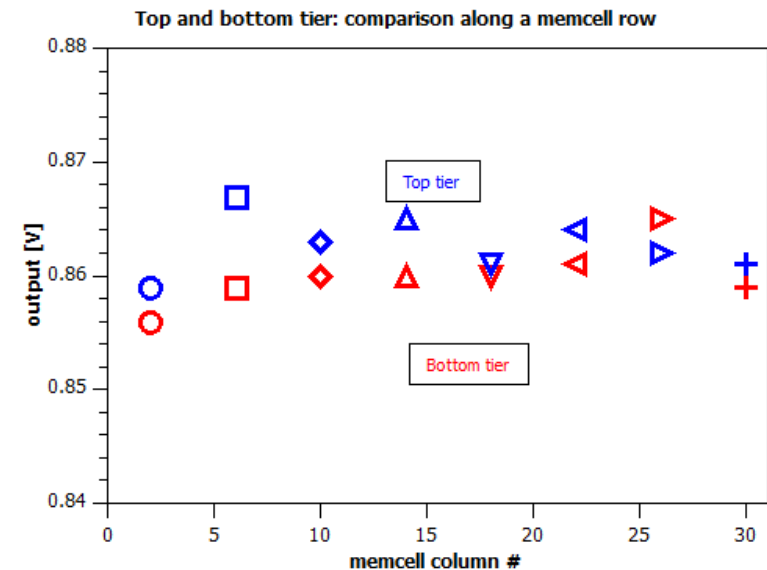


Comparable (linear) detector response

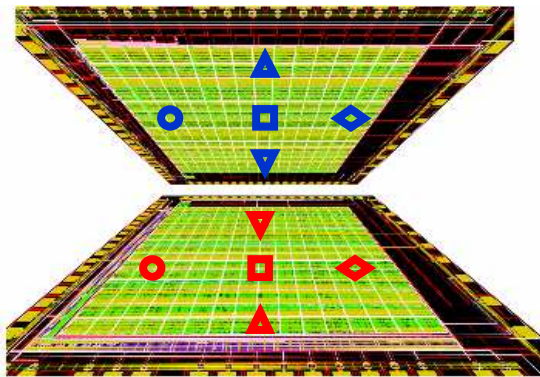
- for charge stored in either in Top/Bottom tier
- for different memory cells in the same pixel

Slight pedestal offset, to be investigated further

8/10 samples ok



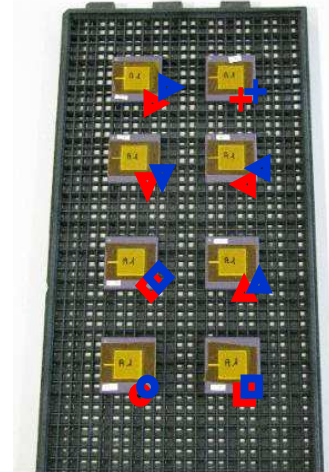
Top/Bottom tier: pixel-to-pixel & chip-to-chip variations



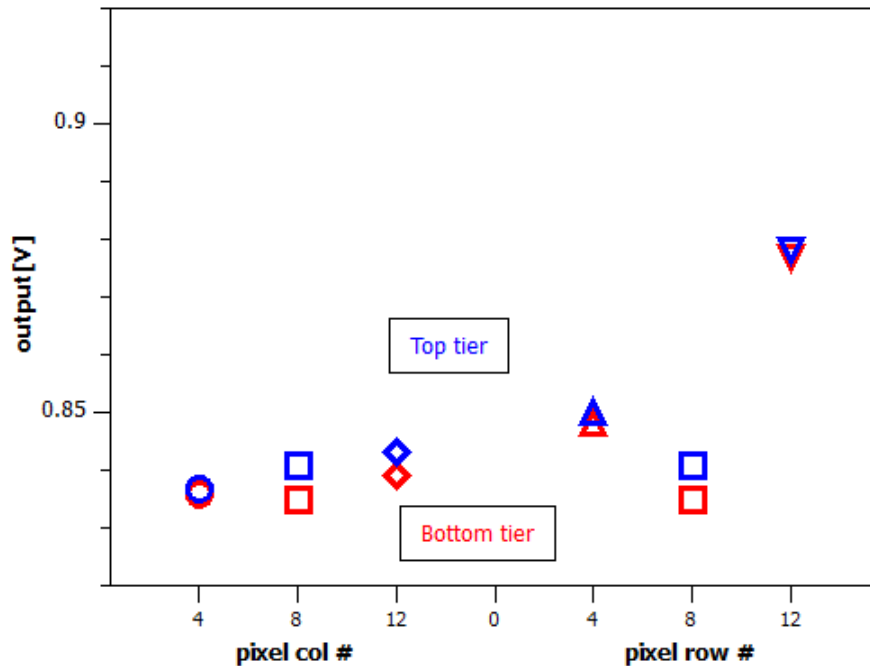
Different pixels/samples: slightly higher variations. However, outputs from memory cells in the Top/Bottom tier of the same pixel remain similar.

Process parameter dispersion in the active pixel circuitry is suspected.

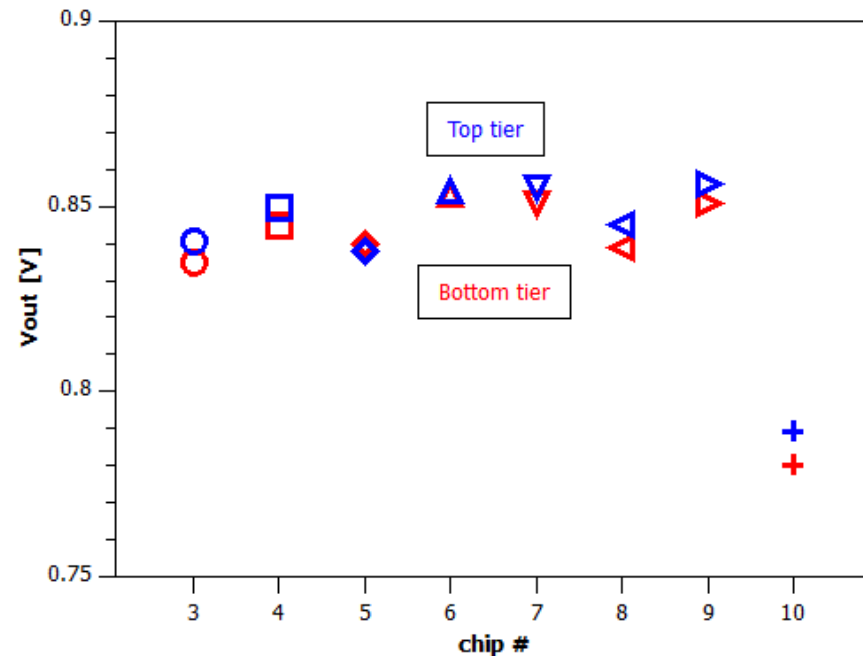
Per-pixel calibration in any case needed.



Top and bottom tier: comparison along a pixel row / column



Top and Bottom tier: comparison among different chips



Conclusion



Extending photon science detectors in the third dimension:

- the 3D-AGIPD case

Prototype produced: T13C11 3DIC MPW run (through CMP)

- GF130nm tech, Tezzaron 3D-process, 2 tiers, face-to-face
- 256 pixel array (200um, 544 images memory depth) + test structures

First evaluations

- good TSV, tier-to-tier contact characteristics (100% of tested)
- 8/10 samples with pixel array working as expected

Experience → pros and cons of this approach to vertical integration

- long turnover times, delays
- limited availability out of US
- presently: 2 tiers

- ✓ it works
- ✓ 2D manufacture, 3D post-processes in one package (transparent to customer)
- ✓ high vert-interconnection density

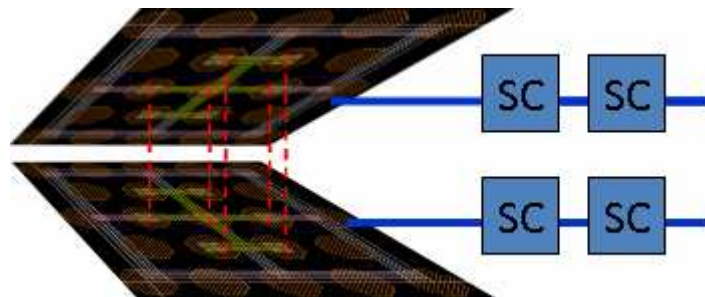
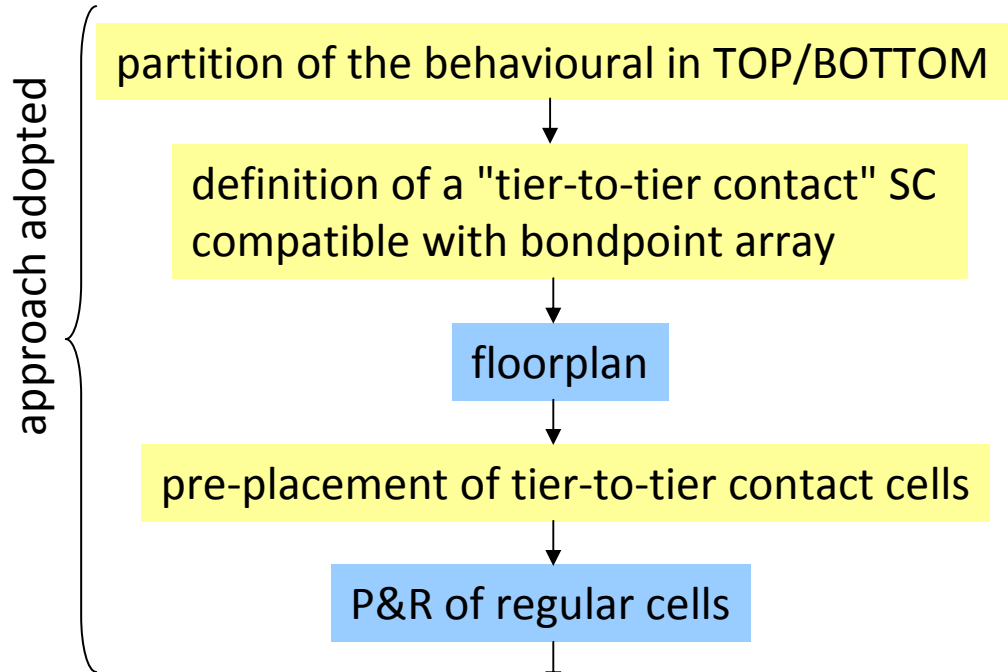


Backup

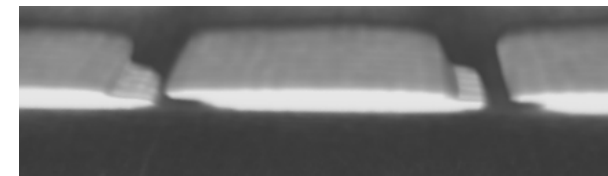
Tier-to-tier contacts



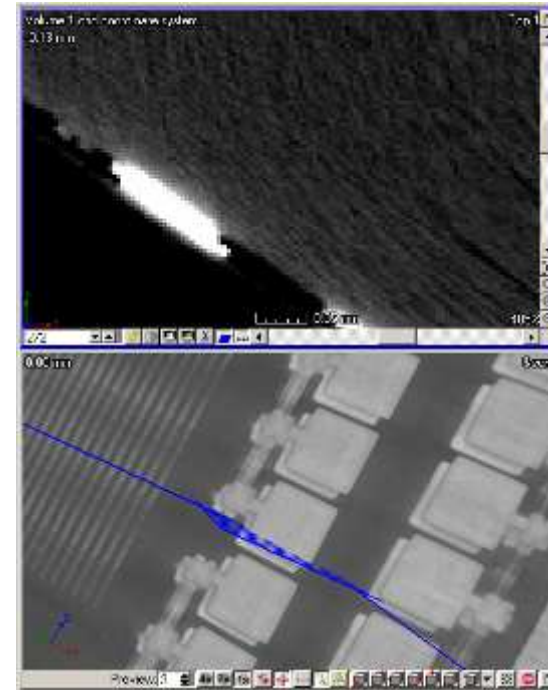
Cu-bondpoints (M6) used for tier-to-tier connectivity



tier-to-tier contact redundancy was suggested by 2009 MPW experience, to counter eventual tier misalignment



however ...



M³APS (courtesy of INFN-Perugia)
submitted end 2009
Tomography by F. Beckmann (DESY)